L Number	Hits	Search Text	DB	Time stamp
1	260	interface adj level adj density	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 22:51
3	27	(heat adj treatment) near (gate adj (insulation or insulating or oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 22:56
4	0	(heat adj treatment) near (gate adj (insulative))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 22:55
5	0	(heat adj treatment) near (gate adj insulant)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 22:55
6	0	(heat adj treatment) near (gox)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 22:55
7	113	temperature near (gate adj (insulation or insulating or oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 23:04
8	0	(heat adj treatment) near (gate adj dielectric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 22:56
10	0	(microwave adj plasma adj cvd) near (gate adj insulating)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 23:06
11	0	(microwave adj plasma adj cvd) near (gate adj insulation)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 23:06
12	0	(microwave adj plasma adj cvd) near (gate adj oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 23:06
13	0	(microwave, adj plasma adj cvd) near (gate adj dielectric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 23:06
14	0	(microwave adj plasma adj cvd) near (gate adj insulative)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 23:07
15	0	(microwave adj plasma adj cvd) near (gox)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/05 23:07